





Development of Air Stable Silicon Photoemitter with Electronically Tunable Negative Electron Affinity

Ragib Ahsan, Hyun Uk Chae, Anika Tabassum Priyoti, Juan Sanchez Vazquez, Rehan Kapadia

> Department of Electrical and Computer Engineering University of Southern California



Can we operate a negative electron affinity photocathode without ultrahigh vacuum?



Traditional Negative Electron Affinity Photocathode



Pros:

- 1. High quantum efficiency
- 2. Visible photon excitation

Cons:

1. Requires ultrahigh vacuum

NEGATIVE ELECTRON AFFINITY

Hernandez-Garcia, Carlos, Patrick G. O Shea, and Marcy L. Stutzman. "Electron sources for accelerators." Physics today61.2 (2008): 44.



Electronically Tunable NEA Photocathode



4

Working Principle



- Voltage is applied between the semiconductor and graphene, generating an electric field which mimics the surface dipole field in an NEA photocathode.
- Photo-excited electrons tunnel through the barrier and introduced into graphene with higher energy than E_{F,Gr}



Experimental results: Emission current vs V_{Gr-Si}



Experimental results: Emission current vs Anode voltage



Stability at higher vacuum pressures



Experimental results: Emission current vs Optical power





Key emission characteristics

- Existence of a threshold V_{Gr-Si} to emit electrons
- Energy distribution of emitted electrons is broad
- Emission current shows a highly nonlinear dependence on optical power



Existence of a threshold V_{Gr-Si}

- The electrons tunneling into/through SiO₂ must gain higher energy than the vacuum level (0.9 eV higher than SiO₂ conduction band minima)
- Direct tunneling of electrons through SiO₂ will never allow this
- Electrons must tunnel into SiO₂ conduction band (FN tunneling)
- These electrons must gain at least 0.9 eV energy from electric field



Threshold for applied voltage



Broad energy distribution

- To have a broad energy distribution, electrons must scatter at SiO₂ conduction band
- Possible scattering mechanisms for SiO₂
 - Longitudinal polar optical phonon scattering
 - Acoustic phonon scattering
 - Impact ionization scattering





Monte Carlo simulation: Transport at SiO₂





Monte Carlo simulation: Transport at SiO₂





Nonlinear emission current

- Multiphoton absorption is highly unlikely in silicon for the optical power densities we have $(10^3-10^4 \text{ W/m}^2)$
- There is no dominant scattering mechanism for SiO₂ that is nonlinear to electron injection rate/optical power
- Optical power must modify the voltage distribution within the device
 - Voltage dropped at depletion region at silicon
 - Voltage dropped at oxide

Voltage distribution between oxide and silicon

- Extremely small electron generation rate (dark/low optical power)
 - No inversion layer can be formed at Si/SiO₂ interface
 - Majority voltage is dropped at silicon depletion layer (V_{Gr-Si} ≈ V_{si} >> V_{ox})
- Moderate electron generation rate (moderate optical power)
 - Incomplete generation of inversion layer
 - Appreciable voltage drop across oxide
- High electron generation rate (high optical power)
 - Complete inversion
 - Majority voltage drop across oxide (V_{Gr-Si} ≈ V_{ox} >> V_{si})
- Poisson's equation determines how much voltage drops across different parts of the device $(V_{Gr-Si} = V_{Si} + V_{ox})$

•
$$V_{si} = \frac{1}{2\epsilon_{si}}qN_A x_{dep}^2 + \frac{1}{\epsilon_{si}}q(g_{dark} + g_{ph})x_{dep}\tau_e$$

17



Voltage redistribution by optical power





Summary

- This is a silicon photocathode
 - Fabrication is easier and cheaper
- NEA surface is controlled by voltage
 - Can be turned on and off
 - Stable at atmospheric conditions
- Photons need to have energy \geq silicon bandgap
 - Visible lasers are enough for emission



Acknowledgements

- Principal investigator: Prof. Rehan Kapadia
- Graduate students: Hyun Uk Chae, Anika Tabassum Priyoti, Juan Sanchez Vazquez, Zezhi Wu
- Sponsors:



